

LETTERS

Reproducible nanostructure fabrication using atomic force microscopy indentation with minimal tip damage

SeungHee Jeon, BongWoo Ryu, Wonho Jhe, Zheong G. Khim and Byung I. Kim
J. Vac. Sci. Technol. B **32**, 020601 (2014); <http://dx.doi.org/10.1116/1.4862538>

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Selective deposition of graphene sheets on a flexible substrate by a nonuniform electric field

Sooyeoun Oh, Hyunik Park, Younghun Jung, Jihyun Kim, Jiwan Kim and Min Suk Oh
J. Vac. Sci. Technol. B **32**, 020602 (2014); <http://dx.doi.org/10.1116/1.4862536>

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Asymmetric resistive switching characteristics of $\text{In}_2\text{O}_3:\text{SiO}_2$ cosputtered thin film memories

Wei-Kang Hsieh, Kin-Tak Lam and Shoou-Jinn Chang
J. Vac. Sci. Technol. B **32**, 020603 (2014); <http://dx.doi.org/10.1116/1.4863915>

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Novel high-throughput and maskless photolithography to fabricate plasmonic molecules

Alireza Bonakdar, Sung Jun Jang and Hooman Mohseni
J. Vac. Sci. Technol. B **32**, 020604 (2014); <http://dx.doi.org/10.1116/1.4865999>

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Quality of development of latent sebaceous fingerprints coated with thin films of different morphologies

Stephen E. Swiontek, Drew P. Pulsifer and Akhlesh Lakhtakia
J. Vac. Sci. Technol. B **32**, 020605 (2014); <http://dx.doi.org/10.1116/1.4867440>

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REVIEW ARTICLES

Helium ion microscopy

Gregor Hlawacek, Vasilisa Veligura, Raoul van Gastel and Bene Poelsema
J. Vac. Sci. Technol. B **32**, 020801 (2014); <http://dx.doi.org/10.1116/1.4863676>

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Heusler nanoparticles for spintronics and ferromagnetic shape memory alloys

Changhai Wang, Judith Meyer, Niclas Teichert, Alexander Auge, Elisabeth Rausch, Benjamin Balke, Andreas Hütten, Gerhard H. Fecher and Claudia Felser
J. Vac. Sci. Technol. B **32**, 020802 (2014); <http://dx.doi.org/10.1116/1.4866418>

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J. Vac. Sci. Technol. B **32**, 021207 (2014); <http://dx.doi.org/10.1116/1.4867356>

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LITHOGRAPHY

Polymethyl methacrylate/hydrogen silsesquioxane bilayer resist electron beam lithography process for etching 25 nm wide magnetic wires

Jean Anne Currivan, Saima Siddiqui, Sungmin Ahn, Larysa Tryputen, Geoffrey S. D. Beach, Marc A. Baldo and Caroline A. Ross

J. Vac. Sci. Technol. B **32**, 021601 (2014); <http://dx.doi.org/10.1116/1.4867753>

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Focused helium and neon ion beam induced etching for advanced extreme ultraviolet lithography mask repair

Carlos M. Gonzalez, Rajendra Timilsina, Guoliang Li, Gerd Duscher, Philip D. Rack, Winand Slingenbergh, Willem F. van Dorp, Jeff T. M. De Hosson, Kate L. Klein, Huimeng M. Wu and Lewis A. Stern

J. Vac. Sci. Technol. B **32**, 021602 (2014); <http://dx.doi.org/10.1116/1.4868027>

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NANOMETER SCIENCE & TECHNOLOGY

Nanostructuring of GaAs with tailored topologies using colloidal lithography and dry etching

Kashif Masud Awan, Reza Sanatinia and Srinivasan Anand

J. Vac. Sci. Technol. B **32**, 021801 (2014); <http://dx.doi.org/10.1116/1.4862976>

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Dewetting of Au/Ni bilayer films on prepatterned substrates and the formation of arrays of supersaturated Au-Ni nanoparticles

Andreas Herz, Dong Wang and Peter Schaaf

J. Vac. Sci. Technol. B **32**, 021802 (2014); <http://dx.doi.org/10.1116/1.4863320>

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Impedance characterization of nanogap interdigitated electrode arrays fabricated by tilted angle evaporation for electrochemical biosensor applications

Dae-Young Jeon, So Jeong Park, Yongha Kim, Min-Ju Shin, Pil Soo Kang and Gyu-Tae Kim

J. Vac. Sci. Technol. B **32**, 021803 (2014); <http://dx.doi.org/10.1116/1.4863512>

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Measurement of periodicity and strain in arrays of single crystal silicon and pseudomorphic Si_{1-x}Ge_x/Si fin structures using x-ray reciprocal space maps

Manasa Medikonda, Gangadhara R. Muthinti, Jody Fronheiser, Vimal Kamineni, Matthew Wormington, Kevin Matney, Thomas N. Adam, Evguenia Karapetrova and Alain C. Diebold

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CMOS field emission devices based on {111} silicon surfaces

Michael Bachmann, Andreas Pahlke, Carolin Axt, Bastian Hinze and Walter Hansch

J. Vac. Sci. Technol. B **32**, 02B105 (2014); <http://dx.doi.org/10.1116/1.4860953>

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HfC(310) high brightness sources for advanced imaging applications

William A. Mackie, Josh M. Lovell, Todd W. Curtis and Gerald G. Magera

J. Vac. Sci. Technol. B **32**, 02B106 (2014); <http://dx.doi.org/10.1116/1.4862444>

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Lateral distribution of field-emitted electrons from a carbon nanofiber array: A theoretical calculation

Stylianos Siontas, Andreas Kyritsakis, John P. Xanthakis, Stefano Iacobucci and Gianni Stefani

J. Vac. Sci. Technol. B **32**, 02B107 (2014); <http://dx.doi.org/10.1116/1.4862237>

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Effect of electron focusing in x-ray sources using LiTaO₃ crystals excited by neodymium-doped yttrium lithium fluoride laser light

Kosuke Nakahama, Michiaki Takahashi, Satoshi Abo, Fujio Wakaya and Mikio Takai

J. Vac. Sci. Technol. B **32**, 02B108 (2014); <http://dx.doi.org/10.1116/1.4864307>

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30TH NORTH AMERICAN MOLECULAR BEAM EPITAXY CONFERENCE (30TH NAMBE 2013)

Carrier lifetime studies in midwave infrared type-II InAs/GaSb strained layer superlattice

Brianna Klein, Nutan Gautam, Elena Plis, Ted Schuler-Sandy, Thomas J. Rotter, Sanjay Krishna, Blair C. Connelly, Grace D. Metcalfe, Paul Shen and Michael Wraback

J. Vac. Sci. Technol. B **32**, 02C101 (2014); <http://dx.doi.org/10.1116/1.4862085>

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Closed-cycle cooling of cryopanel in molecular beam epitaxy

Ryan B. Lewis, Vahid Bahrami-Yekta, Medhaj J. Patel, Thomas Tiedje and Mostafa Masnadi-Shirazi

J. Vac. Sci. Technol. B **32**, 02C102 (2014); <http://dx.doi.org/10.1116/1.4862088>

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Study of thermal stability of distributed Bragg reflectors based on epitaxial rare-earth oxide and silicon heterostructures

Rytis Dargis, Jeffrey Leathersich, [Andrew Clark](#) and Erdem Arkun

J. Vac. Sci. Technol. B **32**, 02C103 (2014); <http://dx.doi.org/10.1116/1.4862951>

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